

1 **Effect of Uniaxial Strain on Low Frequency Raman Modes in Few Layers**

2 **Molybdenum Disulfide**

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8 The effect of uniaxial tensile strain on the shear mode (C mode) and layer breathing mode (LB mode) of
9 few layers MoS₂ were studied. The C mode is doubly degenerated into two sub-peaks as applied strain
10 increases. No measurable Raman shift for the LB mode is observed, while its Raman intensity decreases
11 gradually as the strain increases. In addition, the C and LB modes exhibit distinguished thickness
12 dependence. The C mode shows a clear blue shift as the strain increases, while the LB mode is softened
13 in the process. Moreover, the evolution of C mode with thickness follows an enhanced linear-chain
14 model plus a linear component very well. It implies that the C mode is a better thickness navigator as
15 compared to the L mode.

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18 Molybdenum disulfide (MoS₂) is a kind of typical transition metal dichalcogenide semiconductor with
19 an indirect bandgap of 1.29 eV.^[1] In recent years, atomically thick MoS₂ layers have been fabricated by
20 direct mechanical exfoliation^[2] and chemical vapor deposition^[3]. Few layers MoS₂ films have attracted
21 lots of attention because of its intriguing electronic and optical properties. For instance, the room
22 temperature current on/off ratio of monolayer MoS₂ transistor can reach 10⁸, which is much larger than
23 devices based on graphene.^[4] In addition, excellent photoluminescence is revealed in MoS₂ layers
24 resulting from *d*-orbital related interaction.^[5] Monolayer MoS₂ serving as an inverter in a logical circuit
25 with a larger gain factor than conventional semiconductors.^[6, 7] These fantastic properties of MoS₂ are
26 results from its intrinsic band structure. Bulk MoS₂ is composed of weakly interacting layers by van der
27 Waals' (vdWs) force with a monolayer thickness of 0.65 nm.^[8] In each layer, S-Mo-S covalent bonds

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28 constitute a stable unit, which forms two hexagonal planes of S atoms. An intermediate hexagonal plane
29 of Mo atoms is coordinated through ionic-covalent interaction with the S atoms in a trigonal prismatic
30 arrangement as shown in Figure 1a. As the thickness decreases, MoS₂ undergoes a transition from
31 indirect to a direct bandgap of 1.9 eV in monolayer.^[1, 5, 9] Moreover, the bandgap of few layers MoS₂
32 not only depends on its intrinsic thickness but also the external conditions, such as strain. Strain
33 engineering is a powerful tool to modify the properties of materials, especially for ultrathin materials,
34 which can be used to increase carrier mobility and enhance emission efficiency. Graphene under about
35 1% tensile strain possesses a band gap opening of 300 meV.^[10] Since the few layers MoS₂ is highly
36 elastic and robust, it can easily be strained to modulate its properties. For example, the tensile strain can
37 lead to a transition from direct to indirect bandgap in atomically thick MoS₂ when the strain is up to 1%,
38 while the compressive strain will widen the direct bandgap.^[11-13] Particularly, the mechanism of the
39 strain induced properties results from the distortion of the crystal lattice of 2D materials. Since lots of
40 works have studied the effect of phonon vibration in high frequency in few layer MoS₂ by Raman
41 spectroscopy,^[14-18] the strain dependence of phonon vibration modes in low frequency range has seldom
42 been studied as the Rayleigh line is strong and broad to hinder the fine Raman modes in low frequency.
43 The high frequency modes normally are corresponding to the vibration in intralayer chemical bonds and
44 are stronger than the low frequency ones. In contrast, the low frequency modes result from the vdWs
45 force induced weak layer-layer vibrations with each layer as a whole. Therefore, the low frequency
46 modes are more sensitive to the interlayer coupling and thickness, which has been studied in graphene
47 widely.^[19] Herein, we study the evolution of low frequency Raman modes, i.e. the shear (C mode) and
48 layer breathing modes (LB modes) in few layers MoS₂ under controllable uniaxial strain. It is found that
49 the C mode can split into two sub-peaks as the uniaxial strain rises up like the behavior of the high
50 frequency E_{2g}^1 mode. Most importantly, the strain induced two sub-peaks show opposite Raman shifts.

51 In addition, the C and LB modes are more sensitive than the high frequency modes implying the low
52 frequency modes are better to act as a pointer to the layer number in MoS₂.

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Experimental

55 **Sample fabrication-** Few layers MoS₂ flakes were mechanical exfoliated onto clean silicon wafer
56 (285 nm SiO₂) by Scotch tape from bulk MoS₂ crystal (SPI Supplies). After identification, the MoS₂
57 flakes were transferred onto a PET substrate (121 μm thick) with an area of 24 mm × 20 mm using
58 Polydimethylsiloxane (PDMS) film (from Gel-Pak).^[20] The flexible PET substrate was able to provide
59 controllable uniaxial strain if bended with various curvatures.^[21] Before the transfer of few layers MoS₂
60 flakes, a layer of SU-8 photoresist (~400 nm) was pre-coated on the PET substrate to raise the visibility
61 of the MoS₂ and reducing the surface roughness of the substrate, which can ensure a good adhesion of
62 the MoS₂ flakes on the PET substrate.^[22] The MoS₂ flakes were deposited at the center of the PET
63 substrate as far as possible. As the size of the MoS₂ flakes were much smaller than the thickness of the
64 substrate, the induced strain to the MoS₂ can be assumed to be the same as the strain applied to the PET
65 substrate.^[22] Finally, a ~100 nm thick poly(methyl methacrylate) (PMMA) layer was spin coated onto
66 the MoS₂ flake to prevent the slippage between the sample and the substrate.^[23-25]

67 **Atomic force microscope-** Veeco Multimode 8 was used to determine the thickness of the MoS₂
68 flakes on silicon wafer in tapping mode. The scanning area was ~10 μm² to ensure the AFM image
69 resolution.

70 **Ultralow frequency Raman spectroscopy-** Raman spectroscopy measurement was conducted on Horiba
71 HR800 Raman spectroscopy system. An external diode pumped solid state laser of 488 nm was utilized
72 to excite the sample in the confocal Raman system. A neutral filter was used to attenuate the laser power
73 down to 15 μW on the MoS₂ flakes in order to avoid sample heating. As the effect from Rayleigh line,
74 the ultralow frequency module was employed in the Raman system in order to obtain the modes with

75 frequency lower than 10 cm^{-1} , including three BraggGrate notch filters. We used a 100X objective to
76 make the laser spot size of $1\text{ }\mu\text{m}$. A 1800 grooves/mm grating was chosen to enable a spectral resolution
77 of $\sim 0.6\text{ cm}^{-1}$ at 488 nm.

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Results and discussion

80 There are four first-order Raman active modes in bulk 2H-MoS₂ because of the D_{6h} space group, E_{2g}^1
81 mode (383 cm^{-1}), A_{1g} mode (408 cm^{-1}), E_{2g}^2 mode (32 cm^{-1}) and E_{1g} mode (286 cm^{-1}).^[26, 27] As
82 shown in Figure 1b, the E_{2g}^1 mode is in-plane optical opposite vibration of sulfur atoms and
83 molybdenum atoms against each layer. The A_{1g} mode is assigned as the out of plane optical vibration of
84 sulfur atoms in opposite directions. The E_{2g}^2 mode is also known as the shear mode deriving from the
85 rigid in-plane atomic vibration against neighbor layers. The wavenumber of E_{2g}^2 mode is often lower
86 than 50 cm^{-1} covered by the strong Rayleigh line, which can be rejected under ultralow frequency
87 measurement set up. As for the E_{1g} mode, it is associated with the in-plane opposite vibration of sulfur
88 atoms. However, under backscattering configuration, E_{1g} mode is negligible due to the forbidden
89 selection rule based on the lattice symmetry.^[27]

90 The evolution of normal and ultralow frequency Raman modes dependent on the thickness in various
91 MoS₂ flakes are shown in Figure 2a and 2b respectively. For samples from 3-layer to bulk, a clear red
92 shift ($\sim 0.7\text{ cm}^{-1}$) of E_{2g}^1 mode is observed, but the A_{1g} mode gives an apparent blue shift from 405.7 cm^{-1}
93 ¹ in the 3-layer flake to 408.2 cm^{-1} in the bulk. Normally, as the layer increases, the internal interaction
94 resulting from the vdWs force will become strong and lead to the phonon mode hardening.^[28] In A_{1g}
95 mode, the phonon vibrates along the out of plane direction so that strong vdWs interaction results in the
96 stiffness of lattice vibration, which agrees with the previous studies.^[29] However, the opposite trend of
97 E_{2g}^1 mode can attribute to the influence of stacking induced lattice deformation or long range Coulombic
98 interlayer interaction.^[30] The C mode is directly relative to the thickness of MoS₂ flake because they are

99 directly related to the rigid displacement of the layer themselves. Similarly, the C mode also exhibits
100 thickness dependence. As the layer number (N) increases, the C mode reveals a clear blue shift from
101 22.6 cm^{-1} in the 3-layer sample to 32.4 cm^{-1} in the bulk as shown in Figure 2b. It illustrates that the
102 internal layer interaction make the E_{2g}^2 mode stiffen gradually, which implies that the C mode can be
103 utilized to monitor the thickness of MoS₂. In addition, a broad flat peak centered at 38.3 cm^{-1} is observed
104 in the 3-layer MoS₂ flake and it gradually shifts toward the low wavenumber as the layer increases as
105 shown in Figure 2b (guided by the red dot arrow lines). Moreover, the peak cannot be observed in bulk.
106 Based on the evolution dependent on the thickness of the MoS₂, this broad flat peak can be assigned as
107 the layer breath mode (LB mode).^[31-33] The LB mode represents the rigid layer vibrates perpendicular to
108 the atomic planes, which results from the weakness of the interlayer bonding. Considering the C mode is
109 doubly degenerated, the intensity of C mode should be twice stronger than that of the LB mode meaning
110 that the LB mode is much weaker than the C mode, which has been evident from our results as shown in
111 Figure 2b.

112 The peak position shifts of the two high frequency Raman modes as a function of $1/N$ are plotted in
113 Figure 2c. The variations of Raman shift for A_{1g} mode is 2.5 cm^{-1} is much larger than that of E_{2g}^1 mode
114 meaning that A_{1g} mode is more sensitive to the N. The difference of Raman shifts ($\Delta\omega$) for the two
115 modes is often used as a pointer to the sample thickness. The $\Delta\omega$ as a function of $1/N$ is fitted by a linear
116 function with a slope of $-9.69 \text{ cm}^{-1}/N^{-1}$ as shown in the inset of Figure 2c.

117 The rigid layer modes exist in layered crystal where strong and weak forces coexist. They are directly
118 related to the intralayer vdWs forces. The relationship between the C mode and N in graphene has been
119 illustrated by a linear- chain model,^[19]

$$120 \quad \omega = \frac{1}{\sqrt{2\pi c}} \sqrt{\frac{\alpha}{\mu}} \sqrt{1 + \cos\left(\frac{\pi}{N}\right)} \quad (1)$$

121 where c is the speed of light ($3.0 \times 10^{10} \text{ cm/s}$), μ is the unit layer mass per unit area, and α is the
 122 interlayer force constant per unit area. Here, the relationship is also used to illustrate the evolution of C
 123 mode in few layers MoS₂. As shown in Figure 2d, the peak position of C mode is extracted from the
 124 flakes as a function of the reciprocal of N . The solid dot points for a given thickness derive from the
 125 experiment results from different MoS₂ samples. The red dash dot line is the fitting curve using equation
 126 (1). The value of $\frac{\alpha}{\mu}$ is $1.69 \times 10^6 \text{ s}^{-2}$. However, the fitting is not satisfactory as lots of experimental
 127 points deviate from the fitting line. In Ref. 21, graphene is free-suspended on 2~5 μm holes so that no
 128 interaction between the bottom and the substrate is considered into the fitting. However, our few layers
 129 MoS₂ flakes were deposited onto PET substrate. Weak vdWs interaction must exist between the MoS₂
 130 and PET substrate. As the hardening of C mode is due to an increase of the overall restoring force, the
 131 weak vdWs force between MoS₂ and substrate also should be taken into consideration which acts as an
 132 additional spring constant in the linear chain model. In order to fit the experimental data better, a
 133 modified linear chain model is used by adding a linear component, $k \times \frac{1}{N}$, as follows,

$$134 \quad \omega = \frac{1}{\sqrt{2}\pi c} \sqrt{\frac{\alpha}{\mu}} \sqrt{1 + \cos\left(\frac{\pi}{N}\right)} + k \frac{1}{N} \quad (2)$$

135 The fitting curve is given by the blue dash dot line as shown in Figure 2d. It is found that the fitting
 136 using equation 2 is much better than that of equation 1. The fitting parameters $\frac{\alpha}{\mu}$ and k are 1.75×10^6
 137 and -13.4 cm^{-1} respectively, which are similar to the values obtained by equation 1. It implies that the
 138 linear-chain model part is almost the same and that the additional linear component is ascribed to the
 139 weak vdWs interaction between the MoS₂ flake and the PET substrate.

140 Figure 3a shows the optical image of the MoS₂ flakes deposited on the PET substrate. The laser spot
 141 is mainly focused on the area highlighted by the red dashed circle. After all the experiments, the
 142 thickness of this flake was determined as 8.71 nm by atomic force microscope as shown in the inset of
 143 Figure 3b. The morphology of the MoS₂ flake is quite flat with clear edges. The strain was applied to

144 the MoS₂ flake by bending the substrate (Figure 1c).^[14, 34-36] The uniaxial strain (ϵ) is applied along the
145 bending direction as indicated by the green arrows. The strain was calculated based on the formula,
146 $\epsilon = \frac{d}{2r}$ where d is the thickness of the substrate and r is the radius of curvature of the bended substrate as
147 shown in the inset of Figure 1c.

148 The E_{2g}^1 and A_{1g} modes of the unstrained MoS₂ are centered at 383.3 cm⁻¹ and 406.7 cm⁻¹
149 respectively. As the strain rises up gradually, the A_{1g} mode maintains its original position as shown in
150 Figure 4a. Though the strain breaks the crystal symmetry, the atomic displacement of A_{1g} mode is
151 perpendicular to the atomic plane and the strain has little effect on the A_{1g} mode. On the contrary, the
152 E_{2g}^1 mode splits into two sub-peaks, the E_{2g}^{1+} and E_{2g}^{1-} as described in literature.^[16, 37] The integrated
153 Raman intensity of A_{1g} mode remains unchanged. The total intensity of E_{2g}^1 mode now splits between
154 E_{2g}^{1+} and E_{2g}^{1-} modes. Moreover, these two sub-peaks show obvious red shifts as the strain increases
155 illustrating that the strain-induced symmetry break leads to phonon softening. The peak positions of the
156 E_{2g}^{1+} and E_{2g}^{1-} modes as a function of strain is shown in Figure 4c. The Raman shift rates are obtained by
157 linear fitting. The Raman shift rates of the two sub-peaks are different. The E_{2g}^{1+} mode shifts by $-1.01 \pm$
158 $0.46 \text{ cm}^{-1}/\%$ strain, while the E_{2g}^{1-} mode shift by a larger rate of $-6.3 \pm 0.74 \text{ cm}^{-1}/\%$ strain. There
159 is no obvious hysteresis between the strain loading and unloading processes proving that no slippage
160 between the MoS₂ and the PET substrate.

161 Figure 4b shows the evolution of C mode on strain. The C mode is relatively less sensitive to strain as
162 compared to the E_{2g}^1 mode. More importantly, a peak splitting (guided by the two black dash dot arrow
163 lines) of the C mode can also be observed. As the strain increases to 0.25%, a small splitting can be
164 observed and the splitting becomes more and more intense when the strain rises up to 0.81%. However,
165 no measurable Raman shift for the LB mode centered at 21.4 cm⁻¹ is observed except the gradually
166 reduced integrated Raman intensity as guided by the red dash dot arrow line as shown in Figure 4b.

167 Unlike the high frequency E_{2g}^1 mode, the two sub-peaks C^+ and C^- modes show opposite variation
168 trends on strain. The C^- mode red shifts before the strain rises up to 0.25% then almost remains at the
169 same position regardless of further increase in strain. In contrast, the C^+ mode shows a gradual blue
170 shift as the strain increases. The peak positions of the C^+ and C^- modes as a function of strain is shown
171 in Figure 4d. The C^+ mode blue shifts for 0.75 cm^{-1} as the applied strain increased to 0.81%, while the
172 C^- mode redshifts by 1.8 cm^{-1} . In the strain range of 0.25-0.81%, the C^- mode almost remains at its
173 original position. This doubly degenerated behavior for C mode may results from the symmetry of lattice
174 vibration. Referring to the E_{2g}^1 mode, the E_{2g}^1 mode involves opposite vibration of two sulfur atoms with
175 respect to the molybdenum atom in plane and the adjacent vibration directions of these atoms are just
176 opposite with each other. Analogously, the E_{2g}^2 mode also consists of opposite vibration between
177 neighboring layers. The two modes belong to the same symmetry.^[27] Therefore, the C mode also splits
178 into two sub-peaks under strain. Though the strain induced split of C mode is not as strong as that in the
179 high frequency E_{2g}^1 mode, the small split demonstrates that strain can distort the lattice symmetry in 2D
180 materials and similar behavior can be observed in various phonon vibration modes with the same
181 symmetry. As the mechanism of opposite Raman shifts for C^+ and C^- modes, it may be attribute to the
182 properties difference between the even and odd layer number in the multilayer MoS_2 .^[32] Further
183 experiments and theoretical calculations are needed to understand the splitting mechanism of the low
184 frequency modes.

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Conclusions

187 In summary, the effect of strain on the shear mode (C mode) and layer breathing mode (LB mode) of
188 few layers MoS_2 was studied comprehensively. Notably, the C mode is also doubly degenerated similar
189 to the E_{2g}^1 mode with respect to the applied strain. Moreover, the two sub-peaks, C^+ and C^- shift
190 oppositely as the strain increases. However, the frequency of LB mode is immune to the uniaxial strain

191 except its integrated Raman intensity. As the strain increases, the intensity of the LB mode weakens
192 gradually. In addition, the C and LB modes are highly sensitive to the layer number of few layer MoS₂.
193 The evolution of the C mode as a function of layer number can be fitted by a linear-chain model with an
194 additional linear component very well. Our findings pave a path to study the mechanism of low-
195 frequency lattice vibration of various two dimensional layered crystals.

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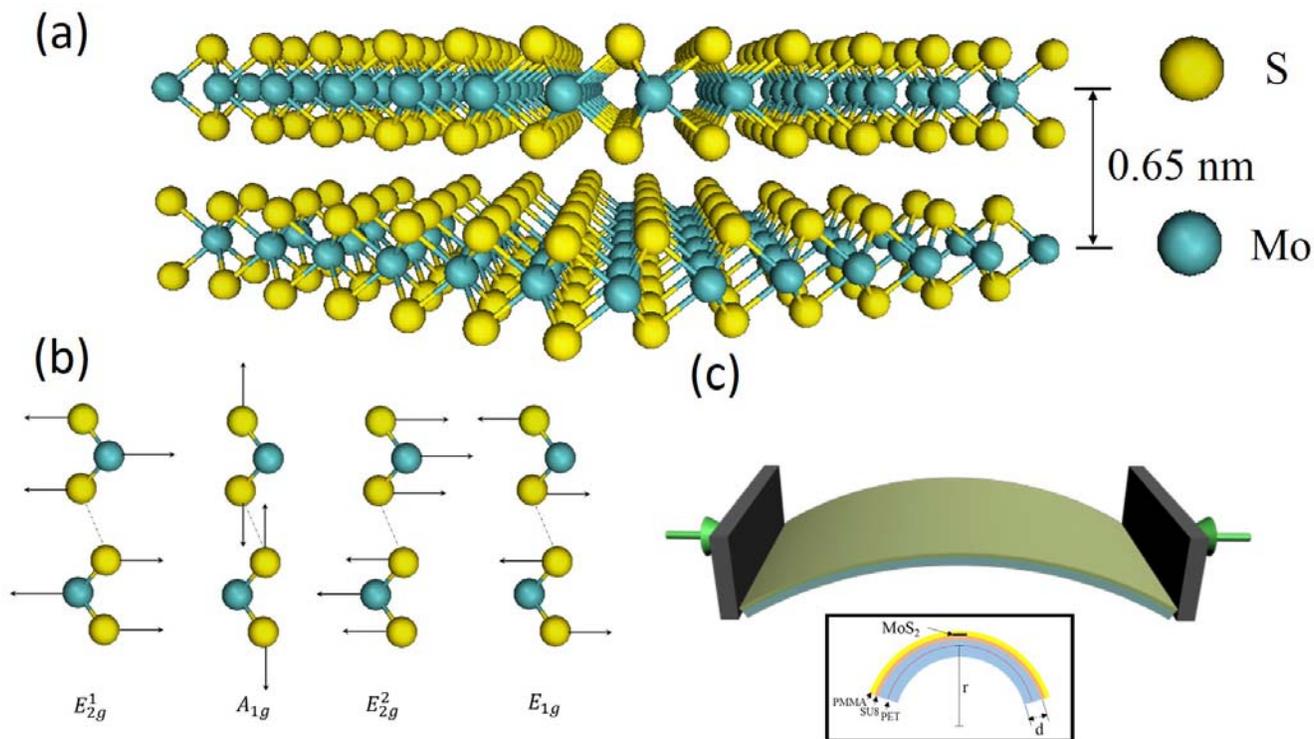
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291 Figure.1 Molecular structures of MoS₂ and the experiment setup. (a) Three dimensional schematic

292 model of the a two-layer MoS₂ structure. The interlayer distance is 0.65 nm. (b) Atomic displacements

293 of the four Raman modes, E_{2g}^1 , A_{1g} , E_{2g}^2 and E_{1g} . (c) Schematic diagram (not to scale) of the

294 experimental setup. Two points bending method is utilized to apply tunable uniaxial tensile strain. The

295 inset shows the cross-sectional view of the PMMA encapsulated few layers MoS₂ on the PET subbtrate.

296 The MoS₂ flake are sandwiched by the bottom SU-8 photoresist layer and the top PMMA layer.

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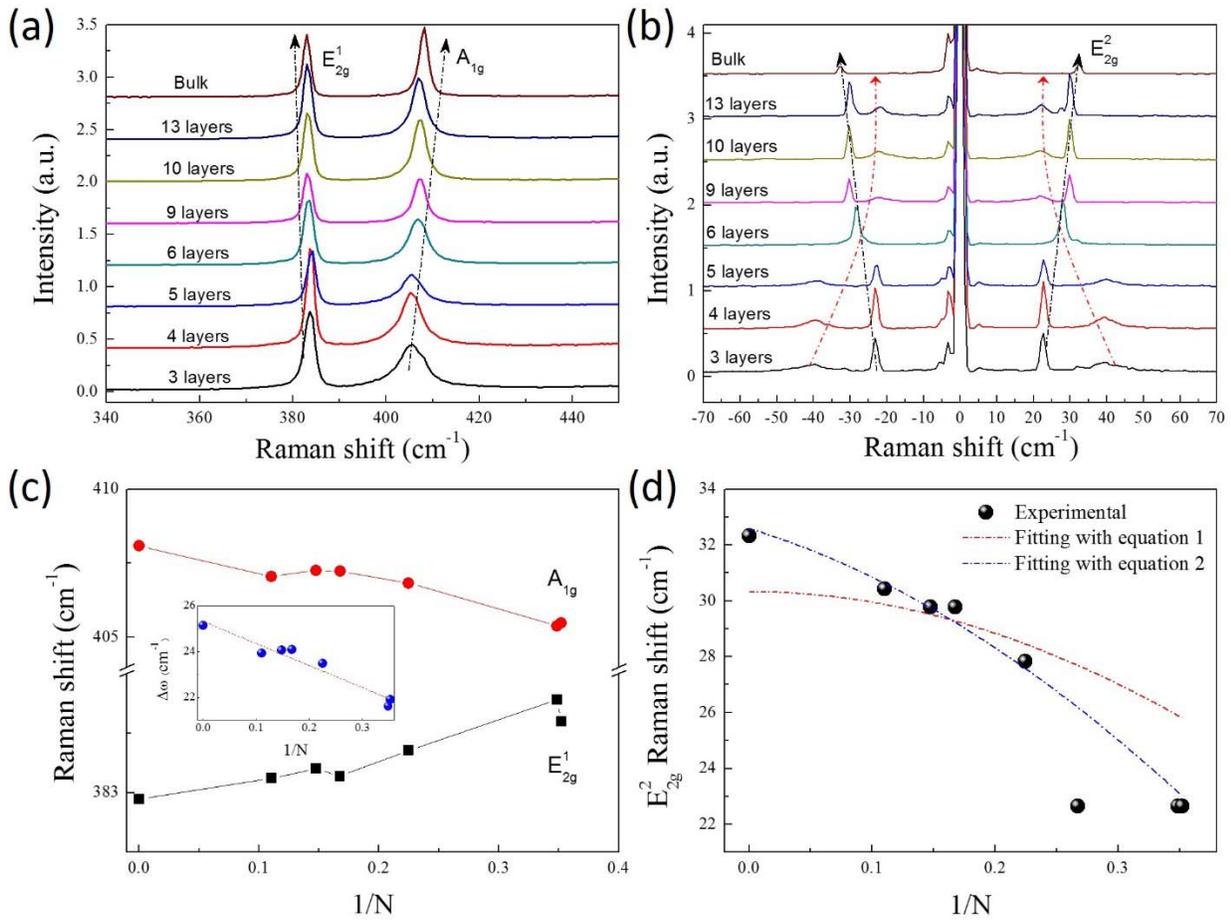
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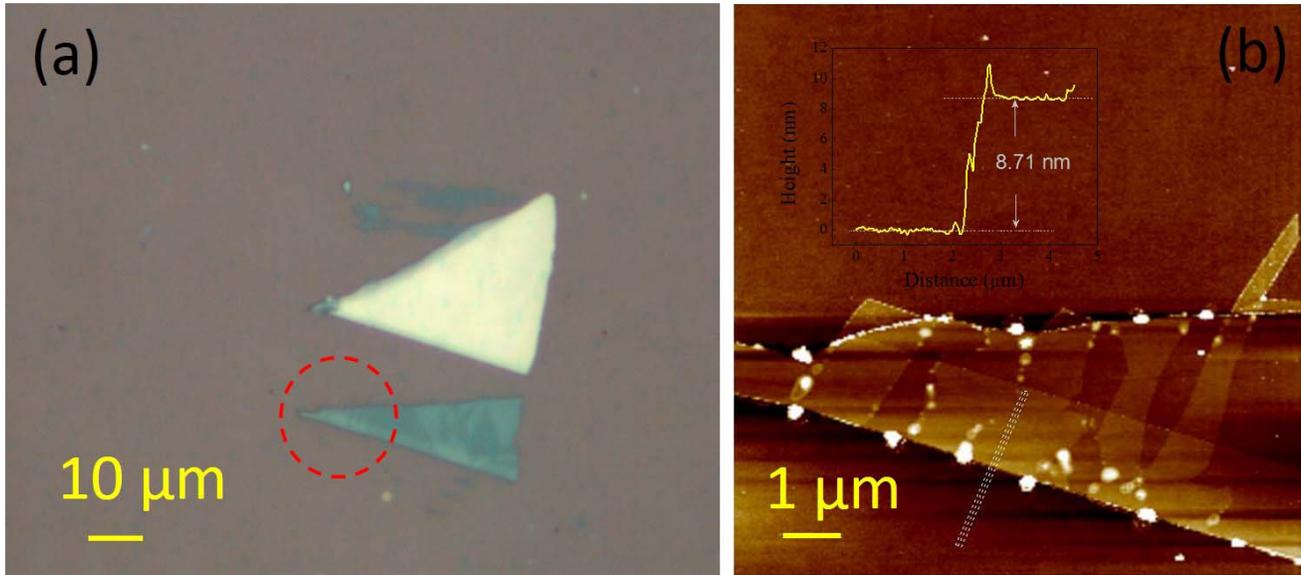
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306 Figure.2 Raman shifts of few layers MoS₂. (a) The evolution of the Raman spectra of the MoS₂ with
 307 different layers. The black dash dot arrow lines are the guide of the peak positions. (b) Raman spectra of
 308 the C and LB modes as a function of the sample thickness. The black and red dash dot arrow lines
 309 represent the C mode and LB mode respectively. (c) The peak positions of the A_{1g} and E_{2g}¹ modes as a
 310 function of the 1/N. The inset gives the trend of the frequency difference of the two modes as a function
 311 of 1/N. (d) Thickness dependence of the Raman shift for the C mode. The black solid dots are
 312 experimental values. The red dash dot line is the fitting with the normal linear-chain model. And the
 313 blue dash dot line is the fitting with a modified model.



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315 Figure.3 (a) Optical image of the few layers MoS₂ deposited onto the flexible PET substrate. The laser
316 spot is positioned at the red dashed circle. (b) AFM image of the MoS₂ flake. The inset shows the
317 thickness of the sample (8.71 nm).

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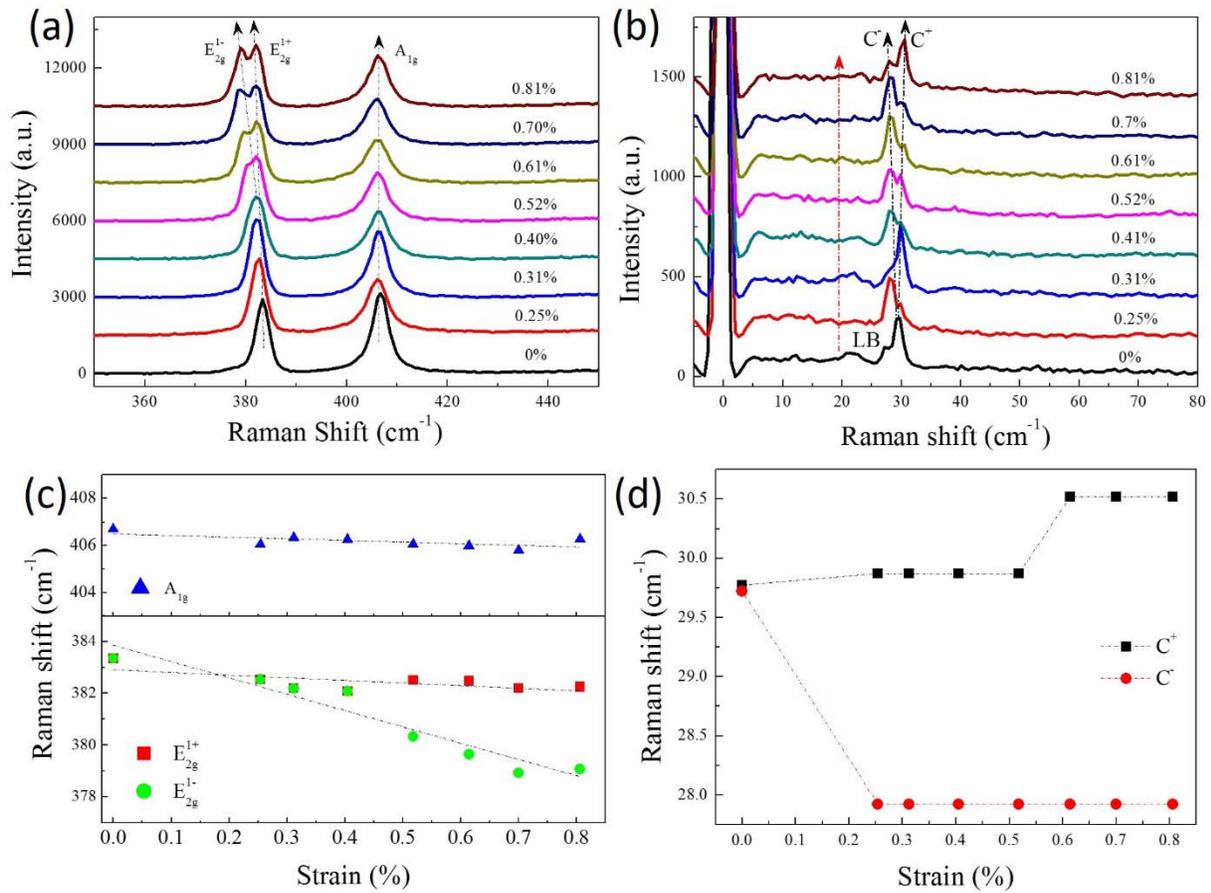
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336 Figure.4 (a) Evolution of the Raman spectra for the E_{2g}^{1+} and A_{1g} modes as a function of strain. The
 337 variation trends of the peak positions are guided by the black dash dot arrow lines. (b) Evolution of the
 338 C and LB modes as a function of strain. The black and red dash dot arrow lines represent C mode and
 339 LB mode, respectively. (c) Strain dependence of the peak positions of E_{2g}^{1+} , E_{2g}^{1-} (lower panel) and A_{1g}
 340 modes (upper panel). The black dash dot lines are linear fitting. (d) The peak positions of the divisive
 341 C^+ and C^- modes as a function of strain.